IE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Takeshi Nogami

Atty. Docket No.

075834.00096

Serial No.:

09/915,145

Group Art Unit:

2811

Filed:

July 25, 2001

Examiner:

Thomas J. Magee

Invention:

"SEMICONDUCTOR DEVICE AND MANUFACTURING METHOD

THEREOF"

AMENDMENT A

Assistant Commissioner of Patents Washington, D.C. 20231

SIR:

In response to the Office Action dated July 3, 2002, please amend the application as follows:

IN THE CLAIMS:

- SECHNOLOGY CENTER 2800

 1. (Once Amended) A semiconductor device comprising:

 a conductive member;

 a cobalt including layer having oxidation resistive and fluorinated acid resistive properties formed over said conductive member; and
- a clad layer formed over the cobalt including layer for cladding said cobalt including layer.
- 2. (Once Amended) The semiconductor device as cited in Claim 1, wherein said cobalt including layer [comprising of the] is comprised of a cobalt tungsten phosphor layer.
- 3. (Once Amended) The semiconductor device as cited in Claim 1, wherein said clad layer [comprising of] is comprised of a cobalt silicide layer.